

A MEMS motion sensor with frequency selective mechanical amplification

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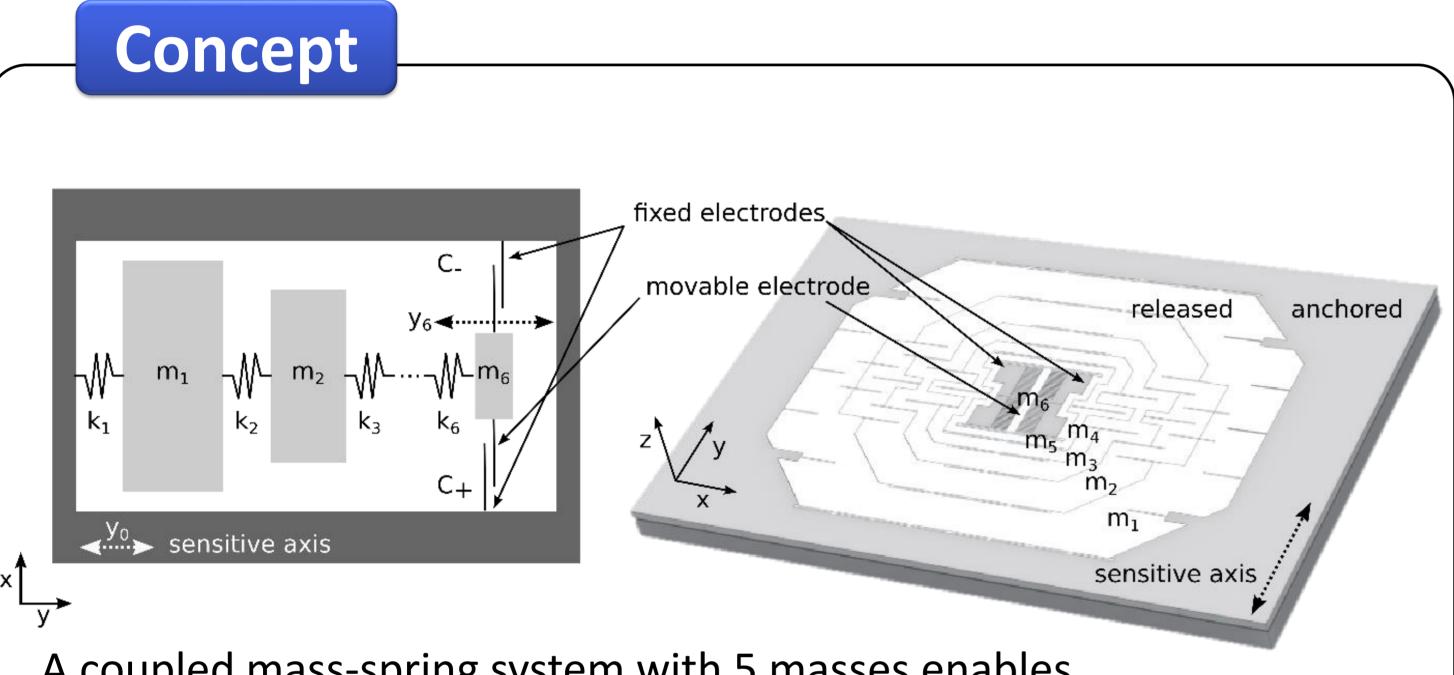
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Motivation

Structural monitoring of geological structures requires the detection of small signals in the low kHz regime. The signals are usually extending over a broad frequency range. State of the art resonant sensors however are restricted to a single resonance and therefore do not respond to the full spectrum of the signal. We propose a broadband motion sensor that amplifies the signal in the frequency range of 3-13 kHz with a minimum (mean) amplification of 16 dB (23 dB) and can be read out capacitively.

Fabrication

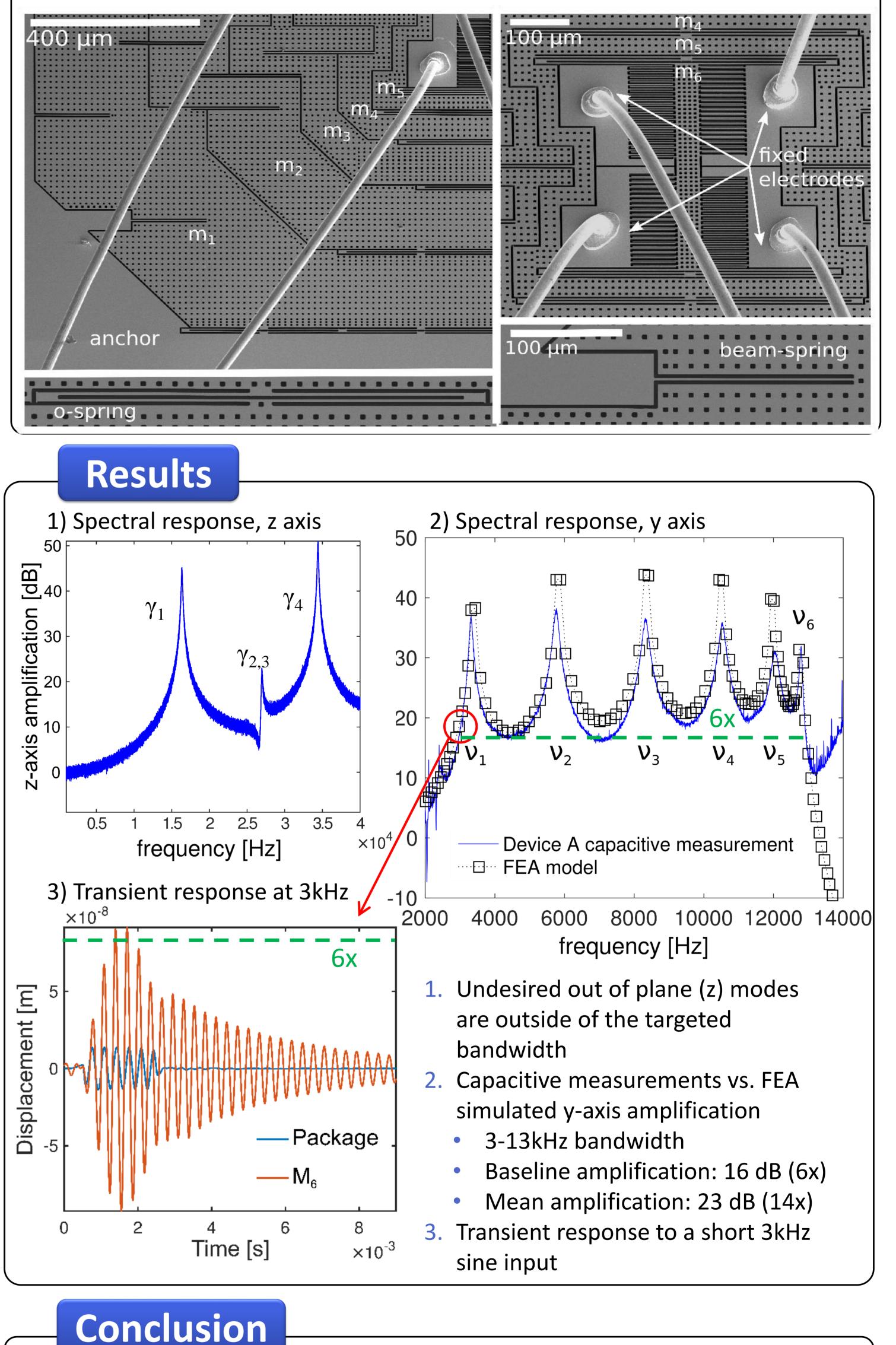
- 5. Dicing 1. PECVD deposition 500 nm SiO₂
- 6. SiO₂ HF vapor release



A coupled mass-spring system with 5 masses enables

- Purely mechanical **amplification** of incoming vibrations
- **Frequency** selectivity

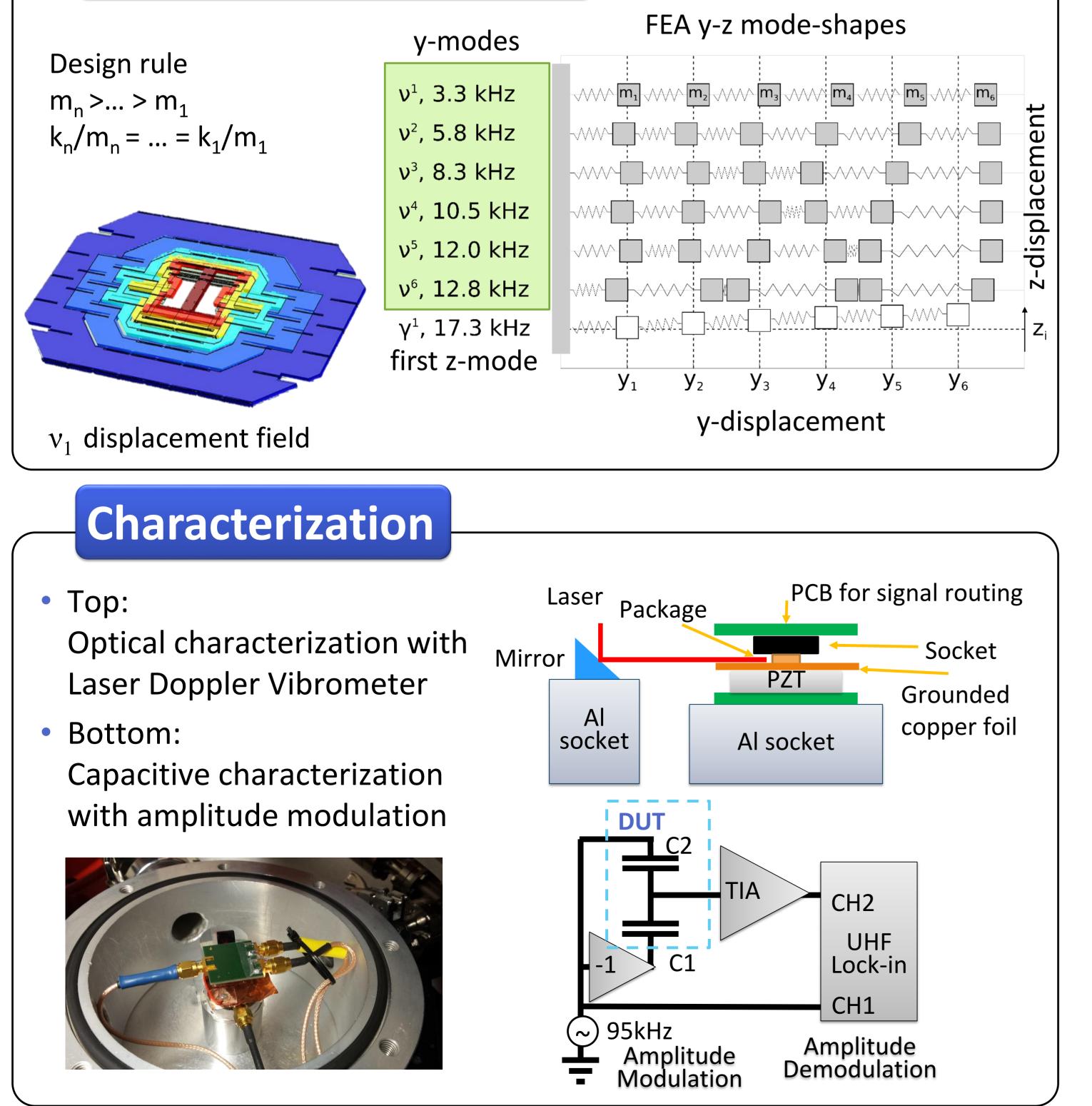
- 2. 1.2 µm Photoresist
- 3. DRIE SiO₂ etch
- 4. ICP Si etch
- 7. Evaporation 4/40 nm Cr/Au
- 8. Die and Wire Bonding

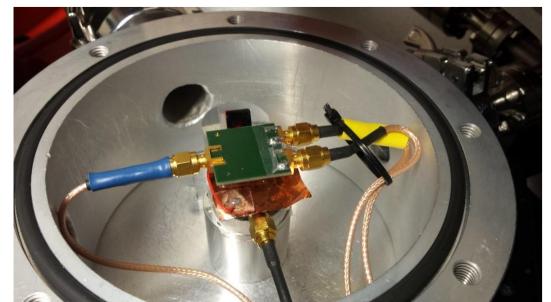


at **zero power** expense

The last mass is connected to a differential capacitance for continuous read out.

Finite Element Analysis





- A MEMS motion sensor with mechanical amplification of minimum (mean) 16 dB (23 dB) within the frequency band of 3-13 kHz was designed, fabricated and characterized
- Z-modes are designed to be outside the target bandwidth for increased axis selectivity
- Transient measurements show that the amplification is reached after only three periods of the input signal, making the device useful for the detection of short acoustic bursts

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